

Amendments to the Specification

At page 1 before the "Technical Field" section, please insert the following:

--RELATED PATENT DATA

This patent resulted from a continuation/divisional application of U.S. Patent Application Serial No. 10/132,767, filed April 24, 2002, entitled "Chemical Vapor Deposition Apparatus", naming Ross S. Dando, Craig M. Carpenter, Philip H. Campbell and Allen P. Mardian as inventors, the disclosure of which is incorporated by reference.--

Please amend the last paragraph starting on page 7 as follows:

A suitable mechanism (not shown) would be associated with subatmospheric transfer chamber 12 for transferring the substrates into and out of the respective processors 14. Further, a vacuum exhaust line/foreline (not shown) would be ~~associate~~ associated with chamber 16 for providing/maintaining desired pressure within the chamber. Of course, the depicted apparatus 10 and processor chambers 14 are only exemplary. The concluding claims are in no way limited by the environment, but for the literal wording appearing in such claims, and without limiting or interpretative reference to the specification or drawings, and in accordance with the doctrine of equivalents.